



Gas Emissions Control and Utilization

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submissions:
closed (1 December 2023)

Message from the Guest Editors

Gas emissions have caused severe environmental issues to human beings. Various physical, chemical, and biological technologies have been employed in efforts toward the reduction and utilization of gas pollutants. This Special Issue is partially associated with the **17th International Conference on Environmental Science and Technology (CEST2021)**. This conference will be held in Athens from 1 to 4 September 2021. The best presentations of the session "Gas Emission Control and Utilization" will be published in this Special Issue, following the normal peer review process. We are pleased to invite you to submit your work in, but not limited to, the following areas:

- Air pollution;
- Gas emission reduction (CO₂, CO, SO₂, H₂S, NO_x);
- Gas utilization and production;
- Gas storage;
- Gas capture and utilization process modeling;
- Gas emissions-related energy and environmental issues.





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Message from the Editor-in-Chief

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